

Applica

## SEARCHED

Class	Sub.	Date	Exmr.
438	689	8/30/02	lh
↓	733	↓	↓
↓	706	↓	↓
↓	691	↓	↓
↓	692	↓	↓

## INTERFERENCE SEARCHED

Class	Sub.	Date	Exmr.

## SEARCH NOTES (INCLUDING SEARCH STRATEGY)

	Date	Exmr.
WEST Keyword search (dielectric And (TEOS or SiN or silicon) And photoresist And (opening or via or hole) and (anisotropic same etch 13)	8/30/02	lh
WEST Keyword (hard mask, dielectric, opening) (barrier layer, opening, dielectric)	9/4/02	a